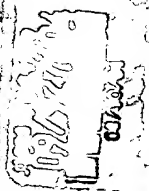


10/10/91



CLASS	ISSUE CLASSIFICATION

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PATENT NUMBER

U.S. UTILITY Patent Application

O.I.P.E.	PATENT DATE
12/11/91 SCANNED HCL	

APPLICATION NO. 09/927604	CONT/PRIOR	CLASS 438	SUBCLASS 120	ART UNIT 2812 2823	EXAMINER F. TOLLOD
TITLE: APPLICANTS Chih-Hsiang Chen Guo-Qiang Lo Shih-Ked Lee					
Gate structures having sidewall spacers using selective deposition and method of forming the same					
PTO-2040 12/99					

ISSUING CLASSIFICATION									
ORIGINAL				CROSS REFERENCE(S)					
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)				
INTERNATIONAL CLASSIFICATION									
<input type="checkbox"/> Continued on Issue Slip Inside File Jacket									

<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>  <input type="checkbox"/> The term of this patent subsequent to (date) has been disclaimed.  <input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent No. _____  <input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
				<b>NOTICE OF ALLOWANCE MAILED</b>	
				<b>ISSUE FEE</b>	
			Amount Due	Date Paid	
			<b>ISSUE BATCH NUMBER</b>		

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